

U.S. Department of Commerce, Patent and Trademark Office (PTO Form 1449 modified)		Docket No. APPM/5269	Serial No. 09/820,586
LIST OF PATENTS AND PUBLICATIONS CITED BY APPLICANT		Applicant Rocha-Alvarez, et al.	Confirmation No.:
(Use several sheets if necessary)		Filing Date March 28, 2001	Group 1763
Examiner Unknown			

## U.S. Patent Documents

*Examiner Initial		Document Number	Issue Date	Applicant(s) Name	Class	Subclass	Filing Date, Appropriate
Thm	A1	6,159,871	12/12/2000	Loboda, et al.	438	786	05/29/1998
	A2	6,147,009	11/14/2000	Grill, et al.	438	780	06/29/1998
	A3	6,140,226	10/31/2000	Grill, et al.	438	637	07/30/1998
	A4	6,124,641	09/26/2000	Matsuura	257	759	12/08/1997
	A5	6,072,227	06/06/2000	Yau, et al.	257	642	07/13/1998
	A6	6,068,884	05/30/2000	Rose, et al.	427	255.6	04/28/1998
	A7	6,054,379	04/25/2000	Yau, et al.	438	623	02/11/1998
	A8	6,054,206	04/25/2000	Mountsier	428	312.8	06/22/1998
	A9	6,040,011	03/21/2000	Yudovsky, et al.	427	255.28	06/24/1998
	A10	6,033,480	03/07/2000	Chen, et al.	118	715	10/15/1996
	A11	6,022,809	02/08/2000	Fan	438	710	12/03/1998
	A12	5,985,033	11/16/1999	Yudovsky, et al.	118	715	07/11/1997
Thm	A13	5,961,774	10/05/1999	Tamura, et al.	156	345	08/01/1997

## Foreign Patent Documents

*Examiner Initial		Document Number	Date	Country	Class	Subclass	Translation	
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Thm	B1	196 54 737 A1	07/03/1997	DE	H01L	21/31	<input checked="" type="checkbox"/>	<input type="checkbox"/>
	B2	198 04 375 A1	01/07/1999	DE	H01L	21/312	<input checked="" type="checkbox"/>	<input type="checkbox"/>
	B3	199 04 311 A1	08/12/1999	DE	C23C	16/44	<input checked="" type="checkbox"/>	<input type="checkbox"/>
	B4	44 04 690 A1	08/17/1995	DE	C23C	16/22	<input type="checkbox"/>	<input checked="" type="checkbox"/>
Thm	B5	0 289 402 A1	11/02/1988	EP	C09D	1/00	<input type="checkbox"/>	<input checked="" type="checkbox"/>

## OTHER ART

*Examiner Initial		Including Author, Title, Date, Pertinent Pages, Etc.
Thm	C1	Tada, et al., "Correlations between Wetting and Structure in Methylsiloxane Layers on Oxides Formed by Chemical Vapor Surface Modification", <i>J. Phys. Chem.</i> 98(47) (1994), pp. 12452-457
Thm	C2	Grill, et al., "Novel Low k Dielectrics Based on Diamondlike Carbon Materials", <i>J. Electrochem. Soc.</i> , 145(5) (May 1998), pp. 1649-1653
Examiner		Date Considered 2/3/03

\*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with your communication to applicant.

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(Use several sheets if necessary)		Filing Date	Group
Examiner Unknown		March 28, 2001	176

## U.S. Patent Documents

*Examiner Initial		Document Number	Issue Date	Applicant(s) Name	Class	Subclass	Filing Date If Appropriate
	A14	5,891,799	04/06/1999	Tsui	438	624	08/18/1997
	A15	5,888,593	03/30/1999	Petrmichl, et al.	427	563	04/12/1996
	A16	5,888,304	03/30/1999	Umotoy, et al.	118	720	04/02/1996
	A17	5,882,419	03/16/1999	Sinha, et al.	118	729	09/29/1997
	A18	5,882,417	03/16/1999	van de Ven, et al.	118	728	12/31/1996
	A19	5,874,367	02/23/1999	Dobson	438	787	06/30/1993
	A20	5,860,640	01/19/1999	Marohl, et al.	269	289R	11/29/1995
	A21	5,858,880	01/12/1999	Dobson, et al.	438	758	05/10/1995
	A22	5,851,299	12/22/1998	Cheng, et al.	118	729	03/25/1994
	A23	5,834,162	11/10/1998	Malba	430	317	10/28/1996
	A24	5,827,408	10/27/1998	Raaijmakers	204	192.12	07/26/1996
	A25	5,821,168	10/13/1998	Jain	438	692	07/16/1997
JAM	A26	5,810,931	09/22/1998	Stevens, et al.	118	721	07/30/1996

## Foreign Patent Documents

*Examiner Initial		Document Number	Date	Country	Class	Subclass	Translation	
							YES	NO
JAM	B6	0 343 502 A2	11/29/1989	EP	H01L	21/00	<input type="checkbox"/>	<input type="checkbox"/>
	B7	0 456 372 A1	11/13/1991	EP	H01L	21/00	<input type="checkbox"/>	<input type="checkbox"/>
	B8	0 456 426 A1	11/13/1991	EP	H01L	21/00	<input type="checkbox"/>	<input type="checkbox"/>
	B9	0 467 623 A2	01/22/1992	EP	C23C	16/54	<input type="checkbox"/>	<input type="checkbox"/>
JAM	B10	0 469 926 A1	08/03/1999	EP	C08J	7/06	<input type="checkbox"/>	<input type="checkbox"/>

## OTHER ART

*Examiner Initial		Including Author, Title, Date, Pertinent Pages, Etc.
JAM	C3	Loboda, et al., "Deposition of Low-K Dielectric Films Using Trimethylsilane", <i>Electrochem. Soc. Proc.</i> , Vol. 98, pp. 145-152
JAM	C4	Nara, et al., "Low Dielectric Constant Insulator Formed by Downstream Plasma CVD at Room Temperature Using TMS/O <sub>2</sub> ", <i>Jap. J. Appl. Phys.</i> , 36 (1997), pp.1477-1480
Examiner		Date Considered 2/3/03

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Examiner Unknown								

U.S. Patent Documents							
*Examiner Initial		Document Number	Issue Date	Applicant(s) Name	Class	Subclass	Filing Date If Appropriate
THM	A27	5,807,785	09/15/1998	Ravi	438	624	08/02/1996
	A28	5,800,877	09/01/1998	Maeda, et al.	427	535	08/09/1996
	A29	5,789,319	08/04/1998	Havemann, et al.	438	668	02/26/1996
	A30	5,766,365	06/16/1998	Umotoy, et al.	118	728	06/07/1995
	A31	5,753,564	05/19/1998	Fukada	437	238	06/07/1995
	A32	5,753,133	05/19/1998	Wong, et al.	216	67	07/11/1994
	A33	5,749,999	05/12/1998	Dandia	156	285	02/04/1994
	A34	5,739,579	04/14/1998	Chiang, et al.	257	635	09/10/1996
	A35	5,738,165	04/14/1998	Imai	165	80.2	06/05/1995
	A36	5,728,276	03/17/1998	Katsuki, et al.	204	298.11	08/21/1995
	A37	5,725,718	03/10/1998	Banholzer, et al.	156	345	08/24/1994
	A38	5,716,486	02/10/1998	Selwyn, et al.	156	345	04/19/1996
THM	A39	5,703,493	12/30/1997	Weeks, et al.	324	755	10/25/1995

Foreign Patent Documents								
*Examiner Initial		Document Number	Date	Country	Class	Subclass	Translation	
							YES	NO
THM	B11	0 489 439 A1	06/10/1992	EP	C23C	16/44	<input type="checkbox"/>	<input type="checkbox"/>
	B12	0 519 079 A1	12/23/1992	EP	H01L	21/312	<input type="checkbox"/>	<input type="checkbox"/>
	B13	0 522 799 A2	01/13/1993	EP	H01L	21/90	<input type="checkbox"/>	<input type="checkbox"/>
	B14	0 533 129 A2	03/24/1993	EP	C23C	16/40	<input type="checkbox"/>	<input type="checkbox"/>
THM	B15	0 589 678 A2	03/30/1994	EP	H01L	23/02	<input type="checkbox"/>	<input type="checkbox"/>

OTHER ART		
*Examiner Initial		Including Author, Title, Date, Pertinent Pages, Etc.
THM	C5	Ducarroi, et al., "SiCN coatings prepared by PACVD from TMS-NH <sub>3</sub> -Ar system on steel", <i>J. de Physique VI</i> , Vol. 3 (August 1993), pp. 247-253
THM	C6	Bunshah, et al., <u>Deposition Technologies for Films and Coatings</u> , Noyes Publications (1982), pp. 339, 357-359 & 366-367

Examiner	Date Considered 2/3/03
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Examiner Unknown		March 28, 2001	1708

**U.S. Patent Documents**

*Examiner Initial		Document Number	Issue Date	Applicant(s) Name	Class	Subclass	Filing Date If Appropriate
	A40	5,703,404	12/30/1997	Matsuura	257	758	12/24/1996
	A41	5,700,720	12/23/1997	Hashimoto	437	195	12/20/1995
	A42	5,693,563	12/02/1997	Teong	437	190	07/15/1996
	A43	5,683,940	11/04/1997	Yahiro	437	195	12/20/1995
	A44	5,679,413	10/21/1997	Petrmichl, et al.	427	534	10/11/1996
	A45	5,665,167	09/09/1997	Deguchi, et al.	118	728	02/14/1994
	A46	5,638,251	06/10/1997	Goel, et al.	361	313	10/03/1995
	A47	5,637,351	06/10/1997	O'Neal, et al.	427	255.3	05/11/1995
	A48	5,632,873	05/27/1997	Stevens, et al.	204	298.15	05/22/1995
	A49	5,632,872	05/27/1997	Dattilo	204	209R	06/21/1995
	A50	5,618,619	04/08/1997	Petrmichl, et al.	428	334	03/03/1994
	A51	5,616,369	04/01/1997	Williams, et al.	427	536	06/24/1994
JHM	A52	5,611,865	03/18/1997	White, et al.	118	725	02/14/1996

**Foreign Patent Documents**

*Examiner Initial		Document Number	Date	Country	Class	Subclass	Translation	
							YES	NO
JHM	B16	0 595 307 A2	05/04/1994	EP	H01L	21/00	<input type="checkbox"/>	<input type="checkbox"/>
	B17	0 598 362 A1	05/25/1994	EP	C23C	14/50	<input type="checkbox"/>	<input type="checkbox"/>
	B18	0 619 381 A1	10/12/1994	EP	C23C	16/00	<input type="checkbox"/>	<input type="checkbox"/>
	B19	0 650 181 A2	04/26/1995	EP	H01J	37/20	<input type="checkbox"/>	<input type="checkbox"/>
JHM	B20	0 688 888 A2	12/27/1995	EP	C23C	16/44	<input type="checkbox"/>	<input type="checkbox"/>

**OTHER ART**

*Examiner Initial		Including Author, Title, Date, Pertinent Pages, Etc.
JHM	C7	McClatchie, et al., "Low Dielectric Constant Oxide Films Deposited Using CVD Techniques", DUMIC Conference (Feb. 16-17, 1998), pp. 311-318
JHM	C8	Loboda, et al., "Using Trimethylsilane to Improve Safety, Throughput and Versatility in PECVD Processes", <i>Electrochem. Proc.</i> Vol. 97-10, pp. 443-453
Examiner		Date Considered 2/3/03

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<b>LIST OF PATENTS AND PUBLICATIONS CITED BY APPLICANT</b>		Applicant Rocha-Alvarez, et al.	Confirmation No.
(Use several sheets if necessary)		Filing Date	Group
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**U.S. Patent Documents**

*Examiner Initial		Document Number	Issue Date	Applicant(s) Name	Class	Subclass	Filing Date If Appropriate
	A53	5,599,740	02/04/1997	Jang, et al.	437	190	11/16/1995
	A54	5,598,027	01/28/1997	Matsuura	257	635	12/21/1995
	A55	5,593,741	01/14/1997	Ikeda	427	579	06/28/1995
	A56	5,578,523	11/26/1996	Fiordalice, et al.	437	190	05/18/1995
	A57	5,574,247	11/12/2001	Nishitani, et al.	118	708	06/21/1994
	A58	5,563,105	10/08/1996	Dobuzinsky, et al.	437	240	09/30/1994
	A59	5,559,367	09/24/1996	Cohen, et al.	257	77	07/12/1994
	A60	5,558,721	09/24/1996	Kohmura, et al.	118	730	11/10/1994
	A61	5,556,476	09/17/1996	Lei, et al.	118	728	10/21/1994
	A62	5,554,570	09/10/1996	Maeda, et al.	437	235	01/09/1995
	A63	5,540,821	07/30/1996	Tepman	204	192.13	07/16/1993
	A64	5,534,110	07/09/1996	Lenz, et al.	156	643.1	07/30/1993

**Foreign Patent Documents**

*Examiner Initial		Document Number	Date	Country	Class	Subclass	Translation	
							YES	NO
	B21	0 708 477 A1	04/24/1996	EP	H01L	21/00	<input type="checkbox"/>	<input type="checkbox"/>
	B22	0 711 817 A2	05/15/1996	EP	C09D	183/04	<input type="checkbox"/>	<input type="checkbox"/>
	B23	0 721 019 A2	07/10/1996	EP	C23C	16/40	<input type="checkbox"/>	<input type="checkbox"/>
	B24	0 721 019 A3	07/27/1997	EP	H01L	21/768	<input type="checkbox"/>	<input type="checkbox"/>
	B25	0 743 675 A1	11/20/1996	EP	H01L	21/316	<input checked="" type="checkbox"/>	<input type="checkbox"/>

**OTHER ART**

*Examiner Initial		Including Author, Title, Date, Pertinent Pages, Etc.
	C9	Horiike, et al., "Filling of Si oxide into a deep trench using digital CVD method", <i>Applied Surface Science</i> , 46 (1990), pp. 164-174
	C10	Noguchi, et al., "Liquid Phase Oxidation Employing O Atoms Produced by Microwave Discharge and Si(CH <sub>3</sub> ) <sub>4</sub> , Extended Abstr. Of 19 <sup>th</sup> Conf. on Solid State Devices and Materials, Tokyo (1987), pp. 451 - 454

Examiner

Date Considered 2/3/03

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## U.S. Patent Documents

*Examiner Initial		Document Number	Issue Date	Applicant(s) Name	Class	Subclass	Filing Date If Appropriate
JPM	A65	5,534,072	07/09/1996	Mizuno, et al.	118	728	06/16/1993
	A66	5,530,581	06/25/1996	Cogan	359	265	05/31/1995
	A67	5,518,593	05/21/1996	Hosokawa, et al.	204	192.12	09/08/1994
	A68	5,516,367	05/14/1996	Lei, et al.	118	725	11/21/1994
	A69	5,508,368	04/16/1996	Knapp, et al.	427	534	03/03/1994
	A70	5,494,712	02/27/1996	Hu, et al.	427	489	11/17/1994
	A71	5,492,736	02/20/1996	Laxman, et al.	427	579	11/28/1994
	A72	5,488,015	01/30/1996	Havermann, et al.	437	195	05/20/1994
	A73	5,476,548	12/19/1995	Lei, et al.	118	728	06/20/1994
	A74	5,474,612	12/12/1995	Sato, et al.	118	725	05/11/1994
	A75	5,468,520	11/21/1995	Williams, et al.	427	560	06/24/1994
JPM	A76	5,468,299	11/21/1995	Tsai	118	730	01/09/1995

## Foreign Patent Documents

*Examiner Initial		Document Number	Date	Country	Class	Subclass	Translation	
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JPM	B26	0 747 934 A1	12/11/1996	EP	H01L	21/00	<input type="checkbox"/>	<input type="checkbox"/>
	B27	0 771 886 A1	05/07/1997	EP	C23C	16/36	<input type="checkbox"/>	<input type="checkbox"/>
	B28	0 774 533 A1	05/21/1997	EP	C23C	16/40	<input type="checkbox"/>	<input type="checkbox"/>
	B29	0 825 279 A1	02/25/1998	EP	C23C	16/44	<input type="checkbox"/>	<input type="checkbox"/>
JPM	B30	0 885 983 A1	12/23/1998	EP	C23C	16/30	<input type="checkbox"/>	<input type="checkbox"/>

## OTHER ART

*Examiner Initial		Including Author, Title, Date, Pertinent Pages, Etc.
JPM	C11	Moriyama, et al., "Thermal Stability of SiN <sub>x</sub> C <sub>y</sub> Films Prepared by Plasma CVD", <i>J. Ceramic Soc. Of Japan</i> , 101(7) (1993), pp. 757-763
JPM	C12	Pierson, <u>Handbook of Chemical Vapor Deposition</u> , Noyes Publications (1992), pp.208-209
Examiner		Date Considered 2/3/03

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**U.S. Patent Documents**

*Examiner Initial		Document Number	Issue Date	Applicant(s) Name	Class	Subclass	Filing Date If Appropriate
	A77	5,466,431	11/14/1995	Dorfman, et al.	423	446	05/25/1994
	A78	5,465,680	11/14/1995	Loboda	117	84	07/01/1993
	A79	5,460,703	10/24/1995	Nulman, et al.	204	192.12	10/03/1994
	A80	5,456,756	10/10/1995	Ramaswami, et al.	118	721	09/02/1994
	A81	5,447,570	09/05/1995	Schmitz, et al.	118	728	06/23/1992
	A82	5,439,524	08/08/1995	Cain, et al.	118	723 E	04/05/1993
	A83	5,437,752	08/01/1995	Lang	156	210	04/04/1994
	A84	5,421,401	06/06/1995	Shertsinsky, et al.	165	80.2	01/25/1994
	A85	5,403,459	04/04/1995	Guo	204	192.32	05/17/1993
	A86	5,383,971	01/24/1995	Selbrede	118	728	03/11/1992
	A87	5,378,165	01/03/1995	Comerci, et al.	439	188	11/12/1993
	A88	5,376,180	12/27/1994	Mahler	118	728	02/25/1994
TAM	A89	5,374,829	12/20/1994	Sakamoto, et al.	250	453.11	04/25/1994

**Foreign Patent Documents**

*Examiner Initial		Document Number	Date	Country	Class	Subclass	Translation	
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TAM	B31	0 926 715 A2	06/30/1999	EP	H01L	21/3105	<input type="checkbox"/>	<input type="checkbox"/>
	B32	0 926 724 A2	06/30/1999	EP	H01L	21/76	<input type="checkbox"/>	<input type="checkbox"/>
	B33	0 935 283 A2	08/11/1999	EP	H01L	21/312	<input type="checkbox"/>	<input type="checkbox"/>
	B34	2.171.877	09/28/1973	FR	C23C	11/00	<input type="checkbox"/>	<input checked="" type="checkbox"/>
TAM	B35	2 015 983 A	09/19/1979	GB	C03C	17/22	<input type="checkbox"/>	<input type="checkbox"/>

**OTHER ART**

*Examiner Initial		Including Author, Title, Date, Pertinent Pages, Etc.
TAM	C13	Loboda, et al., "Safe Precursor Gas For Broad Replacement of SiH <sub>4</sub> in Plasma Processes Employed in Integrated Circuit Production", <i>Materials Safety Soc. Symp. Proc.</i> , Vol. 447 (1996), pp. 145-151
TAM	C14	Lin, et al., "Plasma Polymerization of Trimethylsilane in Cascade Arc Discharge", <i>J. Appl. Polymer Sci.</i> , Vol. 56 (1997), pp. 1653-65
Examiner		Date Considered 2/6/03

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**U.S. Patent Documents**

*Examiner Initial		Document Number	Issue Date	Applicant(s) Name	Class	Subclass	Filing Date If Appropriate
	A90	5,364,666	11/15/1994	Williams, et al.	427	579	09/23/1993
	A91	5,362,526	11/08/1994	Wang, et al.	427	573	01/23/1991
	A92	5,360,646	11/01/1994	Morita	427	574	09/01/1993
	A93	5,352,493	10/04/1994	Dorfman, et al.	427	530	05/03/1991
	A94	5,352,294	10/04/1994	White, et al.	118	725	01/28/1993
	A95	5,343,938	09/06/1994	Schmidt	165	80.2	12/24/1992
	A96	5,328,722	07/12/1994	Ghanayem, et al.	427	250	11/06/1992
	A97	5,326,725	07/05/1994	Sherstinsky, et al.	437	225	03/11/1993
	A98	5,316,645	05/31/1994	Yamagami, et al.	204	298.06	02/17/1993
	A99	5,316,278	05/31/1994	Sherstinsky, et al.	269	254 R	09/18/1992

**Foreign Patent Documents**

*Examiner Initial		Document Number	Date	Country	Class	Subclass	Translation	
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	B37	01-050,429	02/27/1989	JP	H01L	21/318	<input checked="" type="checkbox"/>	<input type="checkbox"/>
	B38	05-033,119	02/09/1993	JP	C23C	8/26	<input checked="" type="checkbox"/>	<input type="checkbox"/>
	B39	05-267,480	10/15/1993	JP	H01L	21/90	<input checked="" type="checkbox"/>	<input type="checkbox"/>
	B40	06-163,521	06/10/1994	JP	H01L	21/314	<input checked="" type="checkbox"/>	<input type="checkbox"/>

**OTHER ART**

*Examiner Initial		Including Author, Title, Date, Pertinent Pages, Etc.
	C15	Loboda, et al., "Plasma-enhanced chemical vapor deposition of a-SiC:H films from organosilicon precursors", <i>J. Vac. Sci. Technol.</i> , 12(1) (Jan/Feb 1994), pp. 90-96
	C16	Bar-Ilan, et al., "A comparative study of sub-micron gap filling and planarization techniques", SPIE Vol. 2636, pp. 277-288
Examiner	Date Considered 2/3/03	

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U.S. Department of Commerce, Patent and Trademark Office (PTO Form 1449 modified)		Docket No. APPM/5269	Serial No. 09/820,586
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Examiner Unknown			

## U.S. Patent Documents

*Examiner Initial		Document Number	Issue Date	Applicant(s) Name	Class	Subclass	Filing Date If Appropriate
TAM	A100	5,314,724	05/24/1994	Tsukune, et al.	427	489	12/19/1991
	A101	5,304,248	04/19/1994	Cheng, et al.	118	728	01/22/1992
	A102	5,298,587	03/29/1994	Hu, et al.	528	10	12/21/1992
	A103	5,292,554	03/08/1994	Sinha, et al.	427	251	11/12/1992
	A104	5,292,399	03/08/1994	Lee, et al.	156	643	01/08/1992
	A105	5,290,736	03/01/1994	Sato, et al.	437	238	09/24/1991
	A106	5,284,730	02/08/1994	Takei, et al.	430	66	08/06/1992
	A107	5,279,867	01/18/1994	Friedt, et al.	427	583	07/09/1992
	A108	5,267,607	12/07/1993	Wada	165	80.1	05/28/1992
	A109	5,262,029	11/16/1993	Erskine, et al.	204	298.15	11/21/1989
	A110	5,250,473	10/05/1993	Smits	437	238	08/02/1991
TAM	A111	5,246,887	09/21/1993	Yu	437	238	07/10/1991

## Foreign Patent Documents

*Examiner Initial		Document Number	Date	Country	Class	Subclass	Translation	
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TAM	B41	06-168,937	06/14/1994	JP	H01L	21/316	<input checked="" type="checkbox"/>	<input type="checkbox"/>
	B42	08-222,559	08/30/1996	JP	H01L	21/316	<input checked="" type="checkbox"/>	<input type="checkbox"/>
	B43	08-236,518	09/13/1996	JP	H01L	21/316	<input checked="" type="checkbox"/>	<input type="checkbox"/>
	B44	08-279,505	10/22/1996	JP	H01L	21/316	<input checked="" type="checkbox"/>	<input type="checkbox"/>
TAM	B45	08-288,286	11/01/1996	JP	H01L	21/316	<input checked="" type="checkbox"/>	<input type="checkbox"/>

## OTHER ART

*Examiner Initial		Including Author, Title, Date, Pertinent Pages, Etc.
TAM	C17	Wrobel, et al., "Reactivity of Alkylsilanes and Alkylcarbosilanes in Atomic Hydrogen-Induced Chemical Vapor Deposition", <i>J. Electrochem. Soc.</i> , 145(3) (March 1998), pp.1060-65
TAM	C18	Grill, et al., "Diamondlike Carbon Materials as Beol Interconnect Dielectrics: Integration Issues", <i>Electrochem. Soc. Proc.</i> , 98(3), pp. 118-128

Examiner

Date Considered 2/3/03

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Examiner Unknown		March 28, 2001	1763

**U.S. Patent Documents**

*Examiner Initial		Document Number	Issue Date	Applicant(s) Name	Class	Subclass	Filing Date If Appropriate
	A112	5,238,499	08/24/1993	van de Ven, et al.	118	724	05/25/1991
	A113	5,231,690	07/27/1993	Soma, et al.	392	416	03/12/1991
	A114	5,230,741	07/27/1993	Van de ven, et al.	118	728	07/16/1990
	A115	5,228,501	07/20/1993	Tepman, et al.	165	80.1	09/02/1992
	A116	5,226,383	07/13/1993	Baht	118	730	11/09/1992
	A117	5,224,441	07/06/1993	Felts, et al.	118	718	09/27/1991
	A118	5,208,069	05/04/1993	Clark, et al.	427	226	10/28/1991
	A119	5,204,141	04/20/1993	Roberts, et al.	427	255.3	09/18/1991
	A120	5,198,034	03/30/1993	deBoer, et al.	118	725	03/04/1991
	A121	5,182,000	01/26/1993	Antonelli, et al.	204	181.1	11/12/1991
	A122	5,156,881	10/20/1992	Okano, et al.	427	572	04/16/1991
	A123	5,124,014	06/23/1992	Foo, et al.	204	192.32	04/11/1991

**Foreign Patent Documents**

*Examiner Initial		Document Number	Date	Country	Class	Subclass	Translation	
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JHM	B46	09-008,03T	01/10/1997	JP	H01L	21/316	<input checked="" type="checkbox"/>	<input type="checkbox"/>
	B47	09-064,029	03/07/1997	JP	H01L	21/316	<input checked="" type="checkbox"/>	<input type="checkbox"/>
	B48	09-237,785	09/09/1997	JP	H01L	21/316	<input checked="" type="checkbox"/>	<input type="checkbox"/>
	B49	09-251,997	09/22/1997	JP	H01L	21/316	<input checked="" type="checkbox"/>	<input type="checkbox"/>
JHM	B50	09-260,369	10/03/1997	JP	H01L	21/316	<input checked="" type="checkbox"/>	<input type="checkbox"/>

**OTHER ART**

*Examiner Initial		Including Author, Title, Date, Pertinent Pages, Etc.
JHM	C20	Grill, et al., "Diamondlike Carbon Materials as Low-k Dielectrics", Conf. Proc. ULSI XII 1997 Materials Research Society, pp. 417-423
JHM	C21	Dobson, et al., "Advanced SiO <sub>2</sub> Planarization Using Silane and H <sub>2</sub> O <sub>2</sub> ", <i>Semiconductor International</i> , (Dec. 1994), pp. 85-88

Examiner

Date Considered 2/3/03

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**U.S. Patent Documents**

*Examiner Initial		Document Number	Issue Date	Applicant(s) Name	Class	Subclass	Filing Date If Appropriate
TAM	A124	5,120,680	06/09/1992	Foo, et al.	437	238	07/19/1990
	A125	5,119,761	06/09/1992	Nakata	118	725	12/21/1990
	A126	5,093,153	03/03/1992	Brochot, et al.	427	41	02/07/1989
	A127	5,040,046	08/13/1991	Chhabra, et al.	357	54	10/09/1990
	A128	5,028,566	07/02/1991	Lagendijk	437	238	07/27/1990
	A129	4,981,724	01/01/1991	Hochberg, et al.	427	255.3	10/27/1988
	A130	4,978,412	12/18/1990	Aoki, et al.	156	345	04/06/1990
	A131	4,973,511	11/27/1990	Farmer, et al.	428	216	12/01/1988
	A132	4,951,601	08/28/1990	Maydan, et al.	118	719	06/23/1989
	A133	4,900,591	02/13/1990	Bennett, et al.	427	255	01/20/1988
	A134	4,894,352	01/16/1990	Lane, et al.	437	238	10/26/1988
	A135	4,892,753	01/09/1990	Wang, et al.	427	38	10/26/1988
TAM	A136	4,872,947	10/10/1989	Wang et al.	156	643	10/26/1988

**Foreign Patent Documents**

*Examiner Initial		Document Number	Date	Country	Class	Subclass	Translation	
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TAM	B51	10-242,143	09/11/1998	JP	H01L	21/316	<input checked="" type="checkbox"/>	<input type="checkbox"/>
	B52	10-242,255	09/11/1998	JP	H01L	21/68	<input checked="" type="checkbox"/>	<input type="checkbox"/>
	B53	11-251,293	09/17/1999	JP	H01L	21/3065	<input checked="" type="checkbox"/>	<input type="checkbox"/>
TAM	B54	59-098,726	12/14/1984	JP	B01J	12/00	<input checked="" type="checkbox"/>	<input type="checkbox"/>

**OTHER ART**

*Examiner Initial		Including Author, Title, Date, Pertinent Pages, Etc.
TAM	C22	Klumpp, et al., "Photoinduced Transformation of Polysiloxane Layer to SiO <sub>2</sub> ", <i>Applied Surface Science</i> , Vol. 43 (1989), pp. 301-303
TAM	C23	Bogart, et al., "Plasma enhanced chemical vapor deposition of SiO <sub>2</sub> using novel alkoxysilane precursors", <i>J. Vac. Sci. Technol.</i> , 13(2) (Mar/Apr 1995), pp. 476-480

Examiner

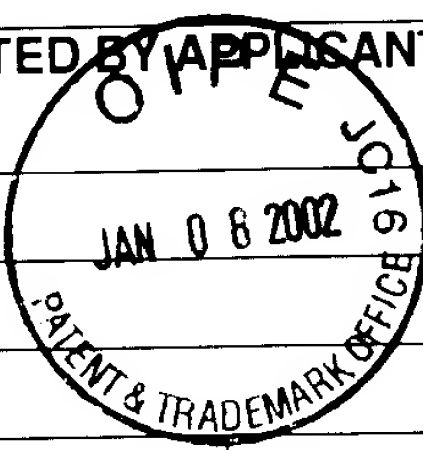
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<b>U.S. Patent Documents</b>								
*Examiner Initial		Document Number	Issue Date	Applicant(s) Name	Class	Subclass	Filing Date If Appropriate	
TAM	A137	4,860,687	08/29/1989	Frijlink	118	500	03/16/1987	
	A138	4,853,102	08/01/1989	Tateishi, et al.	204	298	12/24/1987	
	A139	4,845,054	07/04/1989	Mitchener	437	238	06/29/1987	
	A140	4,842,888	06/27/1989	Haluska, et al.	427	38	04/07/1988	
	A141	4,828,880	05/09/1989	Jenkins, et al.	427	167	12/21/1987	
	A142	4,824,690	04/25/1989	Heinecke, et al.	427	38	11/03/1987	
	A143	4,812,325	03/14/1989	Ishihara, et al.	427	69	10/21/1986	
	A144	4,789,648	12/06/1988	Chow, et al.	437	225	10/28/1985	
	A145	4,798,629	01/17/1989	Wood, et al.	106	287.16	10/22/1987	
	A146	4,707,012	11/17/1987	Takagi	294	64.1	11/03/1986	
	A147	4,603,466	08/05/1986	Morley	29	569R	02/17/1984	
	A148	4,585,920	04/29/1986	Hoog, et al.	219	121 PR	10/09/1984	
TAM	A149	4,579,618	04/01/1986	Celestino, et al.	156	345	10/29/1984	
<b>Foreign Patent Documents</b>								
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TAM	B55	59-222,659	12/14/1984	JP	F16H	9/18	<input checked="" type="checkbox"/>	<input type="checkbox"/>
	B56	60-111,480	06/17/1985	JP	H01L	33/00	<input checked="" type="checkbox"/>	<input type="checkbox"/>
	B57	61-099,149	05/17/1986	JP	G03G	5/082	<input checked="" type="checkbox"/>	<input type="checkbox"/>
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TAM	B59	90/13687	11/15/1990	WO	C30B	25/10	<input type="checkbox"/>	<input type="checkbox"/>
<b>OTHER ART</b>								
*Examiner Initial		Including Author, Title, Date, Pertinent Pages, Etc.						
TAM	C24	Matsuura, et al., "Novel Self-planarizing CVD Oxide for Interlayer Dielectric Applications", IEDM 94 (1994), pp. 117 - 120						
TAM	C25	Gaillard, et al., "Silicon dioxide chemical vapor deposition using silane and hydrogen peroxide", J. Vac. Sci Technol., 14(4) (Jul/Aug 1996), pp. 2767 - 2769						
Examiner					Date Considered 2/3/03			
*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with your communication to applicant.								



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Examiner Unknown								



U.S. Patent Documents							
*Examiner Initial		Document Number	Issue Date	Applicant(s) Name	Class	Subclass	Filing Date If Appropriate
THM	A150	4,557,946	12/10/1985	Sacher, et al.	427	41	06/03/1983
	A151	4,473,455	09/25/1984	Dean, et al.	204	298	03/14/1983
	A152	4,458,746	07/10/1984	Holden, et al.	165	80 A	05/25/1982
	A153	4,268,330	05/19/1981	Komatsu, et al.	156	111	12/26/1979
	A154	4,209,357	06/24/1980	Gorin, et al.	156	643	05/18/1979
	A155	4,168,330	09/18/1979	Kaganowicz	427	39	10/13/1977
	A156	3,955,163	05/04/1976	Novak	355	132	06/24/1974
	A157	3,355,078	11/28/1967	Smith	228	44	11/23/1964
THM	A158	RE. 31053	10/12/1982	Firtion, et al.	355	77	05/01/1988

Foreign Patent Documents								
*Examiner Initial		Document Number	Date	Country	Class	Subclass	Translation	
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THM	B60	92/12535	07/23/1992	WO	H01L	21/312	<input type="checkbox"/>	<input checked="" type="checkbox"/>
	B61	94/01885	01/20/1994	WO	H01L	21/316	<input type="checkbox"/>	<input type="checkbox"/>
	B62	94/01597	01/20/1994	WO	C23C	16/04	<input type="checkbox"/>	<input type="checkbox"/>
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THM	B64	98/08249	02/26/1998	WO	H01L	21/312	<input type="checkbox"/>	<input type="checkbox"/>

OTHER ART		
*Examiner Initial		Including Author, Title, Date, Pertinent Pages, Etc.
THM	C26	Grill, et al., "Low Dielectric constant films prepared by plasma-enhanced chemical vapor deposition from tetramethylsilane", <i>J. Appl. Phys.</i> , 85(6) (Mar. 15 1999), pp. 3314-18
	C27	Luther, et al., "Planar Copper-Polyimide Back End of the Line Interconnections for ULSI Devices", VMIC Conf. (June 8-9, 1993), pp. 15-21
THM	C28	Rau, et al., "Mechanisms of plasma polymerization of various silico-organic monomers", <i>Thin Solid Films</i> 249 (1994), pp. 28-37

Examiner	Date Considered 2/3/03
----------	------------------------

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Examiner Unknown		March 28, 2001	1763

**U.S. Patent Documents**

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**Foreign Patent Documents**

Foreign Patent Documents								
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	B66	99/38202	07/29/1999	WO	H01L	21/312	<input type="checkbox"/>	<input type="checkbox"/>
	B67	99/41423	08/19/1999	WO	C23C		<input type="checkbox"/>	<input type="checkbox"/>
	THM	B68	99/55526	11/04/1999	WO	B32B	9/04	<input type="checkbox"/>

**OTHER ART**

*Examiner Initial		Including Author, Title, Date, Pertinent Pages, Etc.
THM	C29	Sahli, et al., "Properties of plasma-polysiloxane deposited by PECVD", <i>Mat. Chem. &amp; Phys.</i> 33 (1993), pp. 106-109
	C30	Wrobel, et al., "Oligomeric Products in Plasma-Polymerized Organosilicones", <i>J. Macromol. Sci-Chem.</i> , A20(5&6) (1983), pp. 583-618
	C31	Osada, "Plasma-Exposed Polymerization of Cyclic Organosiloxanes in the Condensed Phase", <i>J. Polymer Sci.</i> , Vol. 19 (1981), pp. 369-374
	C32	Favia, et al., "The role of substrate temperature and bias in the plasma deposition from tetramethylsilane", <i>Plasma Sources Sci. Technol.</i> (1992), pp. 59-66
	C33	Kim, et al., "Deposition of thermally stable, low dielectric constant fluorocarbon / SiO <sub>2</sub> composite thin film", <i>Appl. Phys. Letters</i> , 69(18) (October 1999)
	C34	Hazari, et al., "Characterization of Alternative Chemistries for Depositing PECVD Silicon Dioxide Films", DUMIC Conf. (Feb. 16-17, 1998), pp. 319 - 326
	C35	McCabe, et al., "Large Area Diamond-like Carbon Coatings by Ion Implantation", <i>Surface Engineering Vol. III: Process Technology and Surface Analysis</i> , (1992), pp. 163-172
	C36	Favia, et al., "Plasma Deposition of Thin Films from a Fluorine-Containing Cyclosiloxane", <i>J. Polymer Sci: Part A</i> Polymer Chemistry, Vol. 22 (199?), John Wiley & Sons Inc.
	C37	Wertheimer, et al., "Advances in Basic and Applied Aspects of Microwave Plasma Polymerization", <i>Thin Solid Films</i> 115 (1984), pp. 109-124
THM	C38	Theil, et al., "Carbon content of silicon oxide films.....", <i>J. Vac. Sci. Technol.</i> , 12(4) (Jul/Aug 1994), pp. 1365-1370

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